

## PATENT APPLICATION

# IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Attn: OIPE

Hiroyoshi TOMINAGA et al.

Application No.:

10/500,278

Docket No.:

120214

Filed: June 29, 2004

For:

WAFER DOUBLE-SIDE POLISHING APPARATUS AND DOUBLE-SIDE

POLISHING METHOD

## REQUEST FOR CORRECTION OF PALM RECORDS

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Attached is a photocopy of the original filing receipt on which errors have been corrected in red. These errors are being brought to the attention of the Patent and Trademark Office so that it may correct its records.

Respectfully submitted

William P. Berridge Registration No. 30,024

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WPB:JOC/mlo

Date: March 2, 2005

OLIFF & BERRIDGE, PLC P.O. Box 19928 Alexandria, Virginia 22320 Telephone: (703) 836-6400 DEPOSIT ACCOUNT USE AUTHORIZATION Please grant any extension necessary for entry; Charge any fee due to our Deposit Account No. 15-0461



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FILING OR 371 (c) DATE

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DRAWINGS

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06/29/2004

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25944 OLIFF & BERRIDGE, PLC P.O. BOX 19928

ALEXANDRIA, VA 22320



**CONFIRMATION NO. 9347** 

**FILING RECEIPT** 

OC000000015193300\*

Date Mailed: 02/17/2005

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#### Applicant(s)

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### **Assignment For Published Patent Application**

SHIN-ETSU HANDOTAI CO., LTD; TOKYO, JAPAN

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#### Domestic Priority data as claimed by applicant

This application is a 371 of PCT/JP03/03743 03/26/2003

#### Foreign Applications

JAPAN 2002-91087 03/28/2002 JAPAN 2002-91207 03/28/2002

Projected Publication Date: 05/26/2005

Non-Publication Request: No

Early Publication Request: No

Title

water double - side polishing

Double side polishing device for wafer and double side polishing method

apparatus and double-side polishing

Preliminary Class Method

451

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